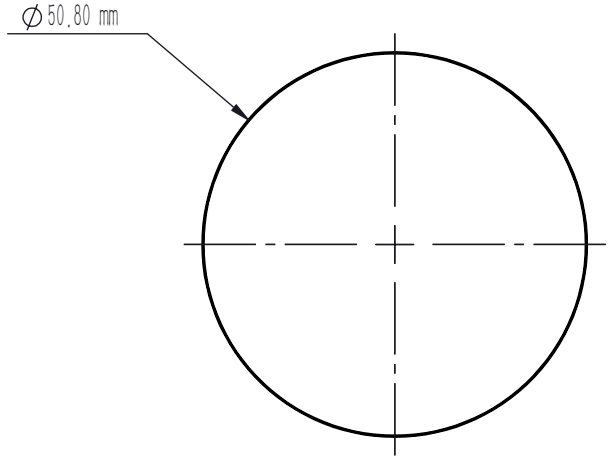

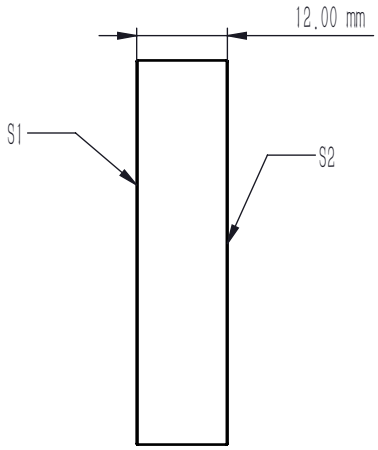

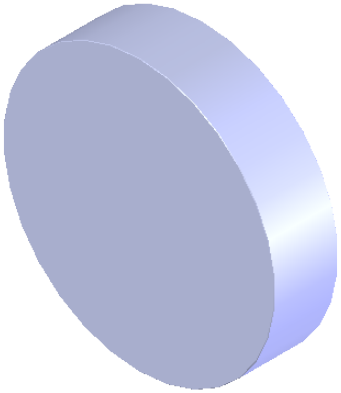

NOTES

1. COATING(S1): LOW GDD COATING
   Rs>99%@340 nm–425 nm, AOI=45° ,
   Rp>99%@360 nm–400 nm, AOI=45° ;
2. GDD:
   |GDDs|<30 fs^2@340 nm–425 nm, AOI=45° ,
   |GDDp|<30 fs^2@360 nm–400 nm, AOI=45° ;
3. CLEAR APERTURE: >90%CA
4. SURFACE QUALITY(S/D)(S1): 20/10
5. SURFACE FLATNESS(S1): λ/10@632.8 nm
6. PARALLELISM(S1,S2): <10 arcsec
7. CHAMFER: < 0.1 mm, 45°
8. THICKNESS TOLERANCE: ±0.1 mm
9. DIAMETER TOLERANCE: +0.0 mm/−0.1 mm
10. BACK SURFACE(S2): POLISHED

DRAWING PROJECTION			LBTEK			
	NAME	DATE	UFPM20–UVB			
DRAWN	ZWANG	JUN./8th/26	ULTRAFAST MIRROR ∅50.8 mm×12 mm, 340–425 nm			
APPROVAL	WCHENG	JUN./8th/26	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	26.5 g	1:1	A